

10/500966

DT15 Rec'd PCT/PTO 08 JUL 2004

THE FOLLOWING IS THE ENGLISH TRANSLATION OF THE ANNEXES TO THE
INTERNATIONAL PRELIMINARY EXAMINATION REPORT: AMENDED SHEETS FOR
2nd ARTICLE 34 (Pages 43,44,45,49/3,49/4,49/5, and 49/6)

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DTI C'd PCT/PTO 08 JUL 2004

What is claimed is:

1. (Amended) A transfer mechanism for transferring substrates to be processed relative to a processing apparatus in a semiconductor processing system, the transfer mechanism comprising:

a transfer base;

a support for supporting the transfer base; and

a first and a second support arm disposed on the transfer base,

wherein the support includes a stretchable and bendable arm that is stretchable and bendable, and

wherein the first and the second support arm respectively have a first and a second support surface for holding the substrates to be processed; the first and the second support surface are positioned on a substantially same plane; and the first and the second support arm are operated such that the first and the second support surface are projected from the transfer base toward a substantially equivalent side.

2. (Canceled)

3. (Canceled)

4. (Amended) The transfer mechanism of claim 1, wherein a

first and a second driving motor for respectively sliding the first and the second support arm and a third driving motor for revolving the transfer base are disposed at an outside of the transfer base, and an axis for revolving the transfer base relative to the support has a three-axis coaxial structure for transferring driving forces of the first to the third driving motors.

5. (Amended) A transfer mechanism for transferring substrates to be processed relative to a processing apparatus in a semiconductor processing system, the transfer mechanism comprising:

a transfer base;

a moving body for linearly moving the transfer base along a loading/unloading port of the processing apparatus; and

a first and a second support arm disposed on the transfer base,

wherein the first and the second support arm respectively have a first and a second support surface for holding the substrates to be processed; the first and the second support surface are positioned on a substantially same plane; and the first and the second support arm are operated such that the first and the second support surface are projected from the transfer base toward a substantially equivalent side, and

wherein the first and the second support arm are alternately disposed in front of the loading/unloading port by a linear motion of the transfer base and alternately access the processing apparatus.

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6.(Amended) The transfer mechanism of claim 5, wherein the moving table and the transfer base are accommodated in a first and a second chamber divided by a sectional plate, and a guide slit for allowing a coupling axis for connecting the transfer base with the moving body to move is formed in the sectional plate.

7.(Amended) The transfer mechanism of claim 6, wherein the first and the second chamber are surrounded by a case; a first and a second driving motor for respectively sliding the first and the second support arm and a third driving motor for revolving the transfer base are disposed at an outside of the case; and the transfer base is connected with the moving body by the coupling axis having a three-axis coaxial structure for transferring driving forces of the first to the third driving motors.

8.(Canceled)

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